

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	("20050185719".)PN	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/28 20:07
L3	1034522	@ad>"20040219"@pt1d>"20040219"@rlad>"20040219"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/28 20:11
L4	2854	438/158,161.ccls. not 3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/28 20:11
L5	1067	(4 four) adj mask not 3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/28 20:12
L6	27	4 and 5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/28 20:39
L7	151	438/161.ccls. not 3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/28 20:17
L8	3	5 and 7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/28 20:17
L9	24	6 not 8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/28 21:42
L10	1	(method and forming and thin adj film adj field adj effect adj transistor and glass adj substrate and buffer adj layer and source and drain adj metal adj regions and defining and opening and silicon adj layer and gate adj oxide adj layer and gate adj metal adj layer and within and first adj photoresist adj pattern and having and two adj portion adj structure and first adj portion and second adj portion and underneath and selectively adj removing adj portions adj gate adj metal and using and selectively and reducing and second adj photoresist adj pattern and coverage adj area adj smaller and reducing and removing and doping and impurity and source adj region and drain adj region and predetermined adj type).clm.	US-PGPUB	OR	ON	2005/12/28 21:48